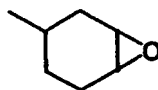


Claims 1- 6 (Canceled).

applying and drying ~~[[a]]~~ the photosensitive composition for optical waveguides;
irradiating said resultant photosensitive composition thin film for optical waveguides
with light through a mask; and
directly forming a core-ridge pattern by wet etching said photosensitive composition thin
film;

$$\left(\text{O}-\text{Si} \begin{array}{c} \text{C}_6\text{H}_4(\text{X}_1)_m \\ | \\ \text{O} \\ | \\ \text{CH}_2 \\ | \\ \text{Z} \end{array} \right)_x - \left(\text{O}-\text{Si} \begin{array}{c} \text{C}_6\text{H}_4(\text{X}_2)_m \\ | \\ \text{O}_{1/2} \end{array} \right)_y \quad (2)$$

(5)



(11)